

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. 26860/33:37 USA	SERIAL NO. 08/276,797
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				APPLICANT Mark D. Owen	GROUP 2106
				FILING DATE July 18, 1994	



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GROUP 2100

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AA						
AB						
AC						
AD						
AE						
AF						

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES
AM	AG 0 5 8 0 4 0 8	01/26/94	EPC	B23K26	00	
AM	AH 630 2 5 9 1 3	02/03/88	Japan	H01L21	20	English Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

AM	AI	"Dopant-Induced Excimer Laser Ablation of Poly(tetrafluoroethylene)," APPLIED PHYSICS B:PHOTO-PHYSICS AND LASER CHEMISTRY, Mar 92, Vol b54, No 3, C R Davis et al, pp 227-230
AM	AJ	"Etch-Stop Polymer Machining with an Argon Ion Laser," IBM TECHNICAL DISCLOSURE BULLETIN, Jan 1993, Vol.36., No. 1, Armonk, NY, US, p. 254
	AK	
	AL	
	AM	
	AN	

EXAMINER	DATE CONSIDERED
Gregory Mills	9-10-96

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.